

Docket No.: 3273-0196PUS1  
(PATENT)

*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

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In re Patent Application of:  
Shigeki KAMBARA, *et al.*

Conf.: 5132

Application No.: 10/519,998

Art Unit: 1752

Filed: January 5, 2005

Examiner: John CHU

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For: PHOTORESIST RESIN AND PHOTORESIST  
RESIN COMPOSITION

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**AMENDMENT UNDER 37 CFR 1.111**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

Responsive to the Office Action of April 6, 2007, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This response includes:

Amended Claim Set; and

Remarks.